

09/927,102



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PATENT

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9/2/05

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION  
METROLOGY SYSTEM  
INTEGRATED INTO  
SEMICONDUCTOR WAFER  
PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO FINAL OFFICE ACTION  
MAILED MARCH 9, 2005**

353 Sacramento St., Suite 2200  
San Francisco, CA 94111  
(415) 772-4900

M/S RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on August 31, 2005.  
STALLMAN & POLLOCK LLP

Dated: 08/31/2005

By:

*Georgia K. Stith*  
Georgia K. Stith

Sir:

In response to the **Final Office Action** mailed March 9, 2005, and in accordance with the accompanying **Request for Continued Examination and Petition for Extension of Time**, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.

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Atty Docket No.: TTI-31000